



Applied Workshop on Dip Pen Nanolithography™

Monday, February 23, 2004

Presented by: Jason Haaheim and Ray Eby, NanoInk, Inc.
Location: Duke University, Hudson Hall Room 222 and
Shared Materials Instrumentation Facility (SMIF) LSRC Room A06

Program:

- 9.30 Registration and welcome (Hudson Hall 222)
- 9.45 Introduction to DPN™ (Hudson Hall 222)
- 10.15 Practical applications applying DPN (Hudson Hall 222)
- 11.00 Products for DPN (Hudson Hall 222)
- 11.15 Inks for DPN – “It’s about the chemistry” (Hudson Hall 222)
- 11.45 Lithographic performance of the NSCRIPTOR™ and the DPN Process (Hudson Hall 222)
- 12.15 MEMS – the manufacturing process (Hudson Hall 222)
- 12.45 Lunch
- 13.45 The NSCRIPTOR “Live” – practical demonstration of DPN (LSRC A06)
- 15.00 Questions and answers (LSRC A06)
- 15.30 End of meeting

For further details on the process and applications of DPN, please visit our web site at www.nanoink.net or email your questions to skosar@nanoink.net
Faculty host at Duke: Dr. Stefan Zauscher, zauscher@duke.edu

Please R.S.V.P. if you plan to attend the workshop!

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